


FORM PTO-1449 (SUBSTITUTE)  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b))				Attorney Docket No.: GR 97 P 1861 Divisional of Applic. No. 09/110,052  Applicant Volker Weinrich et al.  Filing Date of Divisional August 24, 2000 Group Art Unit 2815 <b>1746</b>				1036 U.S. PTO <b>09/645807</b> 	
EXAMINER INITIALS		PATENT NO.	DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE		
SA	A	4,760,481	07/88	Yuito et al.					
	B	5,057,455	10/91	Foo et al.					
	C	5,122,225	06/92	Douglas					
	D	5,208,170	04/93	Kobeda et al.					
	E	5,341,016	08/94	Prall et al.					
	F	5,350,705	09/94	Brassington et al.					
	G	5,515,984	05/96	Yokoyama et al.					
	H	5,562,801	10/96	Nulty					
V	I	5,585,300	12/96	Summerfelt					
FOREIGN PATENT DOCUMENT									
		DOCUMENT NO.	DATE	COUNTRY	CLASS	SUB CLASS	TRANSL. YES   NO		
	J								
	K								
	L								
	M								
	N								
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)									
SA		Patent Abstracts of Japan No. 1-232729 A (Sakota), dated September 18, 1989.							
SA		"Etching of TiN local Interconnects Using HBr in a Triode Reactor with Magnetic Confinement" (Zwicker et al.), Proceedings of the International Society for Optical Engineering, Vol. 1803, 1992, pp. 97-106.							
EXAMINER  <i>Shamun Ahmed</i>				DATE CONSIDERED  <i>3/14/02</i>					
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.									

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EXAMINER INITIALS	PATENT NO.	DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE
SA	A	5,621,606	04/97	Hwang		
SA	B	5,717,236	02/98	Shinkawata		
SA	C	5,883,781	03/99	Yamamichi et al.		
	D					
	E					
	F					
	G					
	H					
	I					

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	DOCUMENT NO.	DATE	COUNTRY	CLASS	SUB CLASS	TRANSL. YES NO	
J							
K							
L							
M							
N							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)		
SA		“Reactive Ion Etching Mechanism of Plasma Enhanced Chemically Vapor Deposited Aluminum Oxide Film in CF <sub>4</sub> /O <sub>2</sub> Plasma” (Kim et al.), J. Applied Physics, Vol. 78, No. 3, August 1995, pp. 2045-49.
SA		“Local Plasma Oxidation and Reactive Ion Etching of Metal Films for Ultrafine Line Pattern Inversion and Transfer” (Nulman et al.), J. Vacuum Science Technology, Vol. B1, Oct.-Dec. 1983, pp. 1033-36.
EXAMINER <i>Shamim Ahmed</i>		DATE CONSIDERED <i>3/14/02</i>

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SA		"WSi <sub>2</sub> /Polysilicon Gate Etching Using TiN Hard Mask in Conjunction with Photoresist" (Tabara), J. Applied Physics, Vol. 36, 1997, pp. 2508-13.					
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Shamim Ahmed				3/14/02			
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